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Supporting information for article:

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In situ energy-dispersive X-ray diffraction of local phase dynamics during solvothermal growth of Cu_4O_3

Supporting Information

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Data Conversion

EDXRD data recorded at APS 6-BM-B were converted by Plot85 to yield data of interplanar spacing (d) vs. intensity (DvsI) for each detector element. A custom script was used to convert the d -spacing into 2θ values as would be recorded using a monochromatic Mo-K $_{\alpha 1}$ X-ray wavelength using Bragg's law $2d \sin \theta = \lambda$, where $\lambda = 0.7093 \text{ \AA}$ and $\theta = 3.25^\circ$. This generated the equivalent 2θ vs. intensity (2θ vsI) data for each detector element.

DvsI and 2θ vsI data for the entire detector were obtained by binning the combined data from the 10 individual detector elements using custom scripts. This was done because the registered values of d within each detector element were irregularly spaced, and because different values of d were registered by different detector elements. Average X-ray intensity from registered d (or 2θ) values within a predefined bin interval was calculated and stored against the middle value of the d (or 2θ) bin. The bin size used for DvsI data was 0.005 \AA , and the bin size used for 2θ vsI data was 0.05° .

Peak fitting

Peak fitting was performed on the binned 2θ vsI data using TOPAS 5.

The CuO (111) peak has partial overlap with a large peak contributed by Cu $_4$ O $_3$ (202) and (004), Cu $_2$ O (111) and CuO ($1\bar{1}\bar{1}$). Because the intensities from Cu $_4$ O $_3$ (202) and Cu $_2$ O (111) dominate the large peak, we deconvoluted this overall peak as two individual peaks. Together with CuO (111), the 2θ range of $14.8\text{--}18.3^\circ$ was fitted by three pseudo-voigt peaks, representing contributions from Cu $_4$ O $_3$ (202) (centered around 16.25°), Cu $_2$ O (111) (centered around 16.47°), and CuO (111) (centered around 17.55°). The fitted areas of Cu $_4$ O $_3$ (202) and Cu $_2$ O (111) are found to be interdependent, thus they are unreliable and not discussed. The values and uncertainties of fitted CuO (111) by TOPAS were extracted.

Cu $_2$ O (200) has partial overlap with Cu $_4$ O $_3$ (220). Therefore, the 2θ range of $18.2\text{--}21.0^\circ$ was fitted by two pseudo-voigt peaks, representing contributions from Cu $_2$ O (200) (centered around 19.22°) and Cu $_4$ O $_3$ (220) (centered around 19.84°). The fitted values and uncertainties were extracted for both peaks.

Cu $_2$ O (224) was fitted by a split-pseudo-voigt peak in the 2θ range of $24.8\text{--}26.6^\circ$. Cu $_2$ O (224) peak center is around 25.91° .

Discussion of powder diffraction intensity

The classical expression for the integrated intensity of a diffraction peak from randomly distributed powder in transmission geometry is given by equation 1:¹

$$P = \left(\frac{e^4}{8\pi m_e^2 c^4} \right) \left(\frac{I_0 \lambda^3}{R} \right) (LP) \left(\frac{m F_T^2}{v_n^2} \right) V \quad (1)$$

where P is the integrated intensity, the terms in the first bracket is a constant of fundamental quantities (e is elementary charge, m_e is electron mass, and c is speed of light), the second term depends on the measurement setup (I_0 is the incident X-ray intensity, λ is X-ray wavelength, and R is the sample-to-detector distance), LP is the Lorentzian-polarization factor ($LP = \frac{1}{\sin \theta \sin 2\theta}$ for vertical scattering plane synchrotron beam, and $LP = \frac{1 + \cos^2 2\theta}{2 \sin \theta \sin 2\theta}$ for unpolarized beam), the term in the fourth bracket depend on the crystal structure of the material (m is multiplicity, F_T^2 is structure factor squared, and v_n is the unit cell volume), and V is the volume of the crystal in the beam.

For normal XRD, scattered intensity is recorded against 2θ so equation 1 (for synchrotron scattering) can be re-arranged as follows to show θ dependence:

$$P(\theta) = \left(\frac{e^4}{8\pi m_e^2 c^4} \right) \left(\frac{I_0 \lambda^3}{R} \right) \left(\frac{1}{\sin \theta \sin 2\theta} \right) \left(\frac{m F_T^2(q)}{v_n^2} \right) V \quad (2)$$

where structure factor F_T is dependent on the length of scattering vector $q = \frac{4\pi \sin \theta}{\lambda}$. This is the equation that Rietveld refinement is based on. Quantitative Rietveld refinement derives sample quantity V from the measured $P(\theta)$ based on structure model.

For EDXRD, scattered intensity is recorded against λ so equation 1 can be re-arranged as follows to show λ dependence:

$$P(\lambda) = \left(\frac{e^4}{8\pi R m_e^2 c^4} \right) \left(\frac{1}{\sin \theta \sin 2\theta} \right) (I_0(\lambda) \lambda^3) \left(\frac{m F_T^2(q)}{v_n^2} \right) V \quad (3)$$

where we have indicated the dependence of incident energy on wavelength, and again F_T has some θ dependence through scattering vector q .

The structure factor $F_T(q)$ has both θ and λ dependence, but its value for one peak is going to be the same in both normal XRD and EDXRD due to its ultimate q dependence. However, for quantitative analysis, one important difference can be seen by comparing equation 2 and equation 3. For different peaks in normal XRD, the I_0 and λ causing diffraction are the same, and the peak intensities are altered by the LP factor. But in EDXRD, LP factor is a constant, but for different peaks, the recorded λ causing diffraction is different,

and so is I_0 .

Because of this difference, even though λ values in EDXRD can be converted into equivalent 2θ in XRD, the dependence of intensity on converted 2θ do not have the same mathematical expression. Most Rietveld refinement algorithms were written based on equation 2 for quantitative analysis and therefore are not suitable to use with quantitative analysis of EDXRD data. Furthermore, we did not obtain precise measurement of I_0 variation with λ .

References

- 1 B. E. Warren, *X-ray diffraction*, Dover Publications, Reprint edn, 1990.

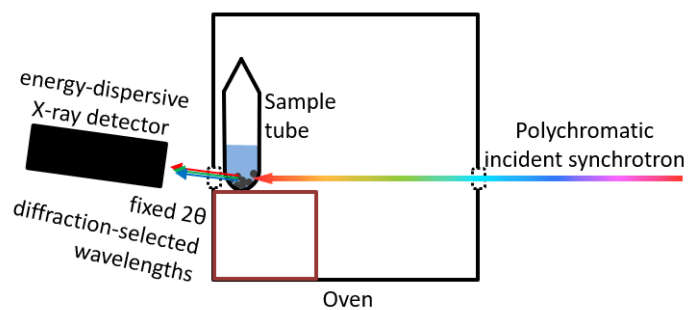


Figure S1 Schematic drawing of the EDXRD setup used in this study.

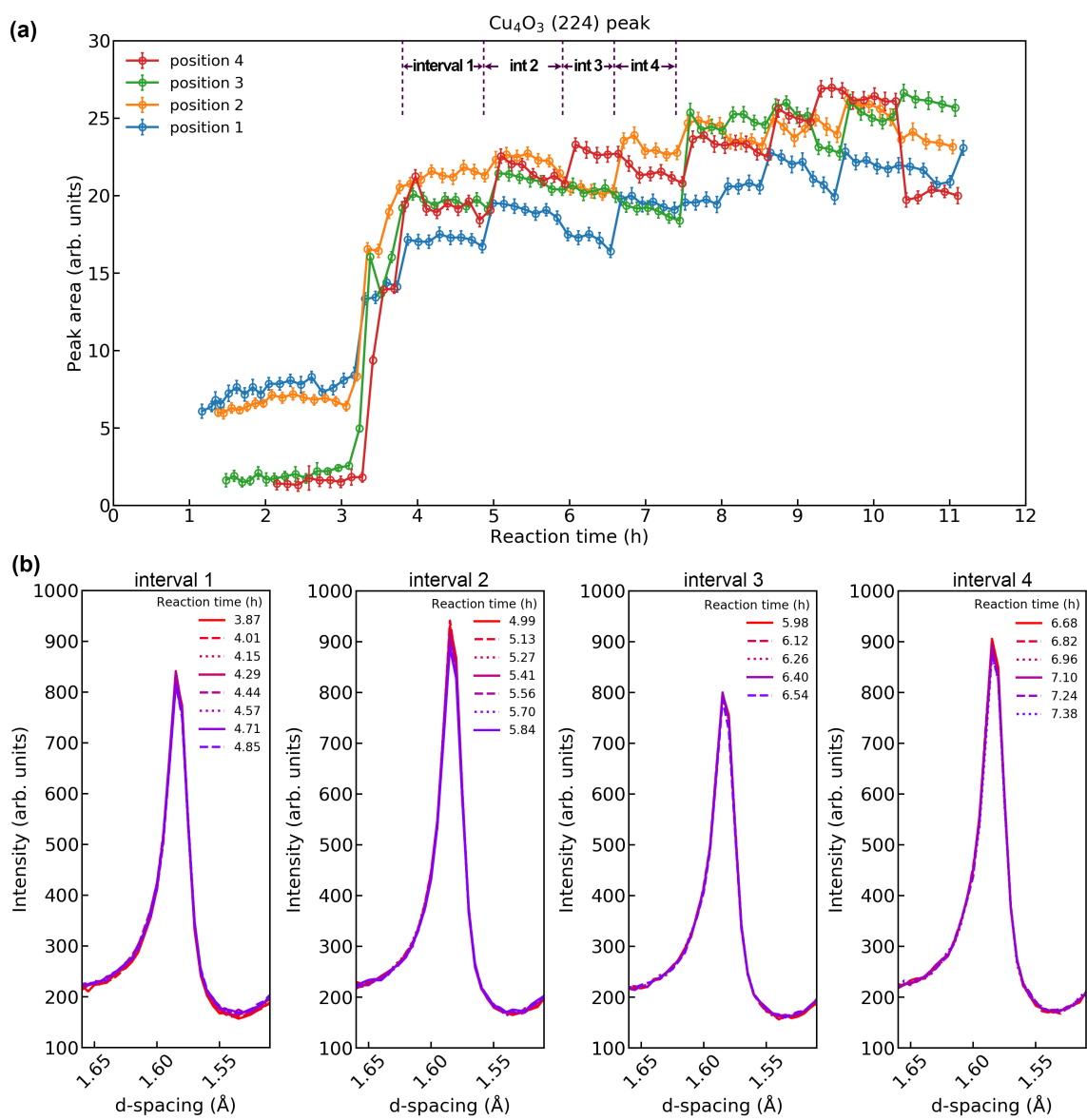


Figure S2 (a) Changes in the fitted Cu_4O_3 (224) peak area with reaction time for four positions during in situ EDXRD investigation. (b) Direct visualizations of the Cu_4O_3 (224) peak at position 1 during the time intervals indicated in (a).

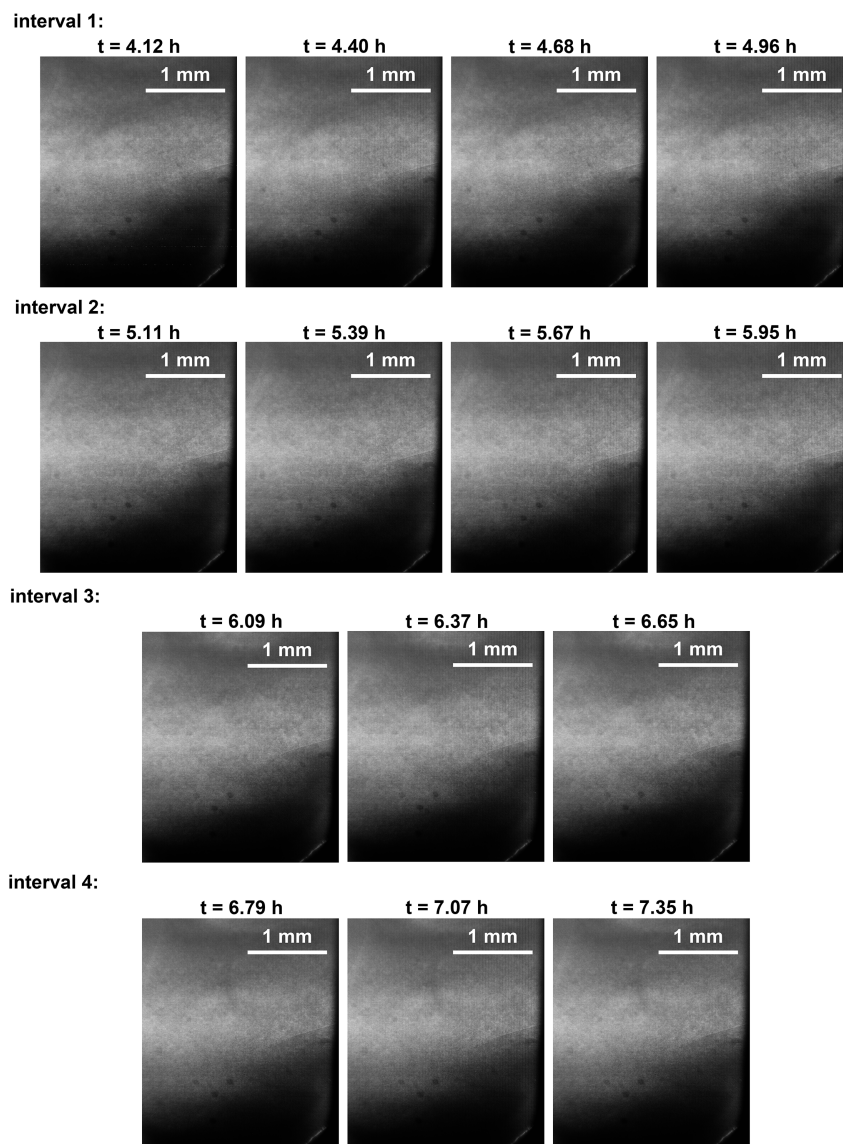


Figure S3 Some radiography images taken during different time intervals discussed in the main article. Radiography images within each interval have no discernible differences. However, some changes can be seen in the images from different intervals due to physical redistribution of the powders caused by bubble formation.

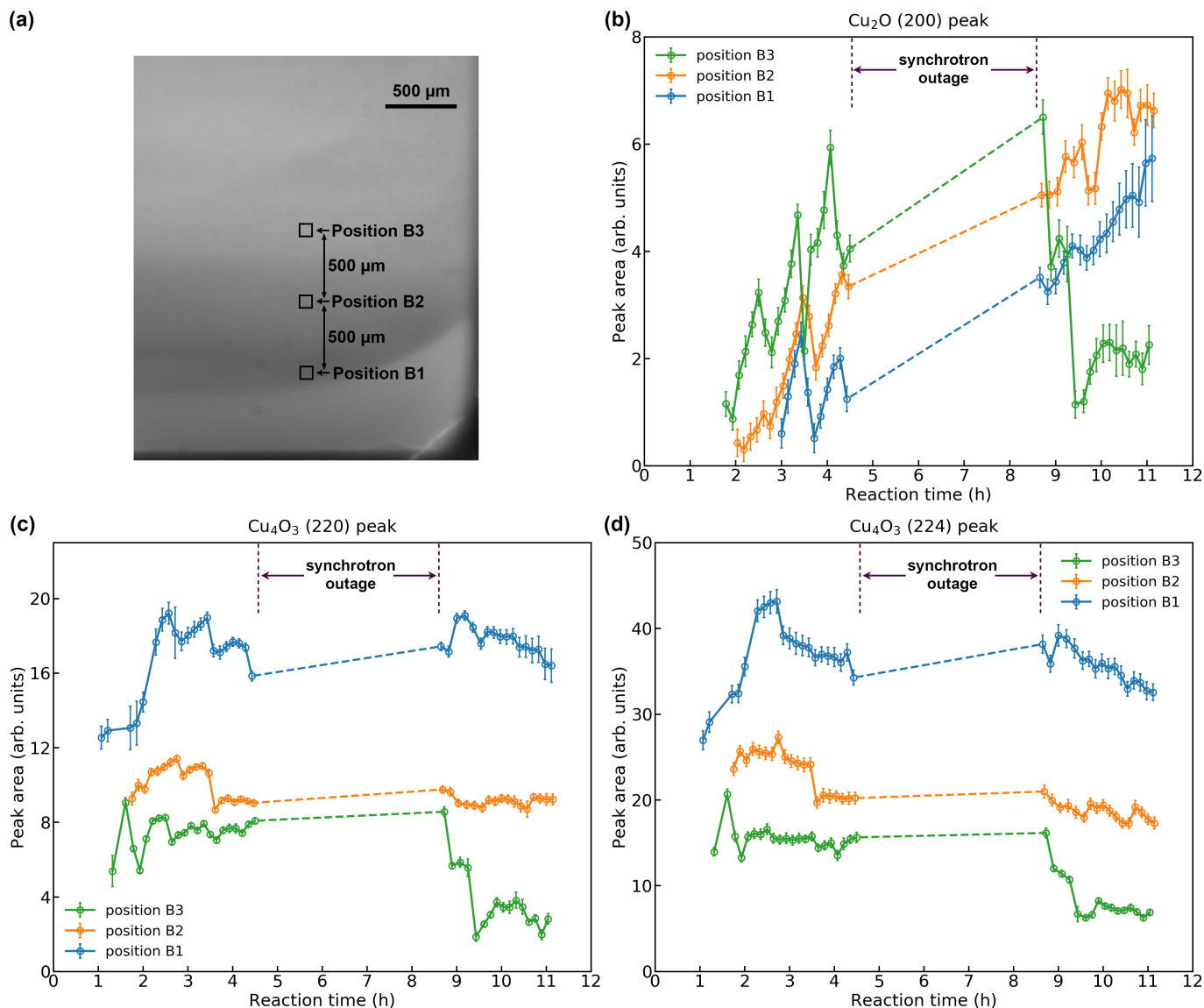


Figure S4 In situ EDXRD was performed for a different sample tube. (a) A radiography image showing the positions where in situ EDXRD signals were collected. The positions are 500 μm apart vertically. Results of the fitted (b) Cu₂O (200), (c) Cu₄O₃ (220), and (d) Cu₄O₃ (224) peak areas during in situ EDXRD for these positions. There was a synchrotron outage during the middle of this investigation, whose duration is shown with dashed lines.

This sample had solvent composed of 33 vol% DMF and 67 vol% ethanol in contrast to the 20 vol% DMF sample discussed elsewhere. This small change of solvent composition has some effect on the balance between the precipitation phases but no change on the solvothermal reaction mechanisms. Because of having more reducing agent DMF, the amount of CuO formed in this sample was too small for CuO (111) to be reliably fitted, so it is not shown. The long-term changes during active in situ EDXRD periods have comparable trends with that during the period without X-rays.